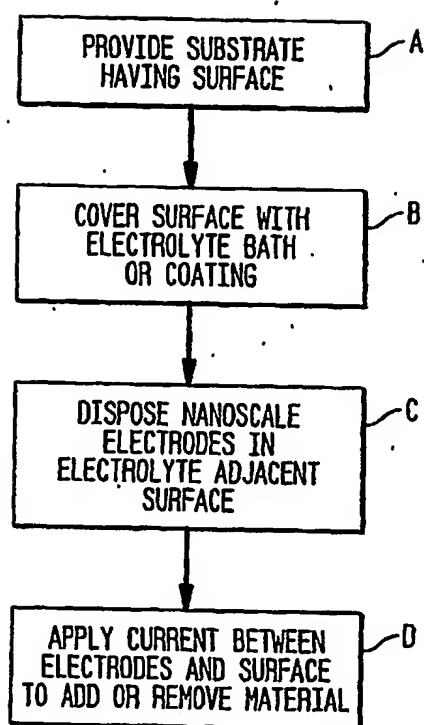


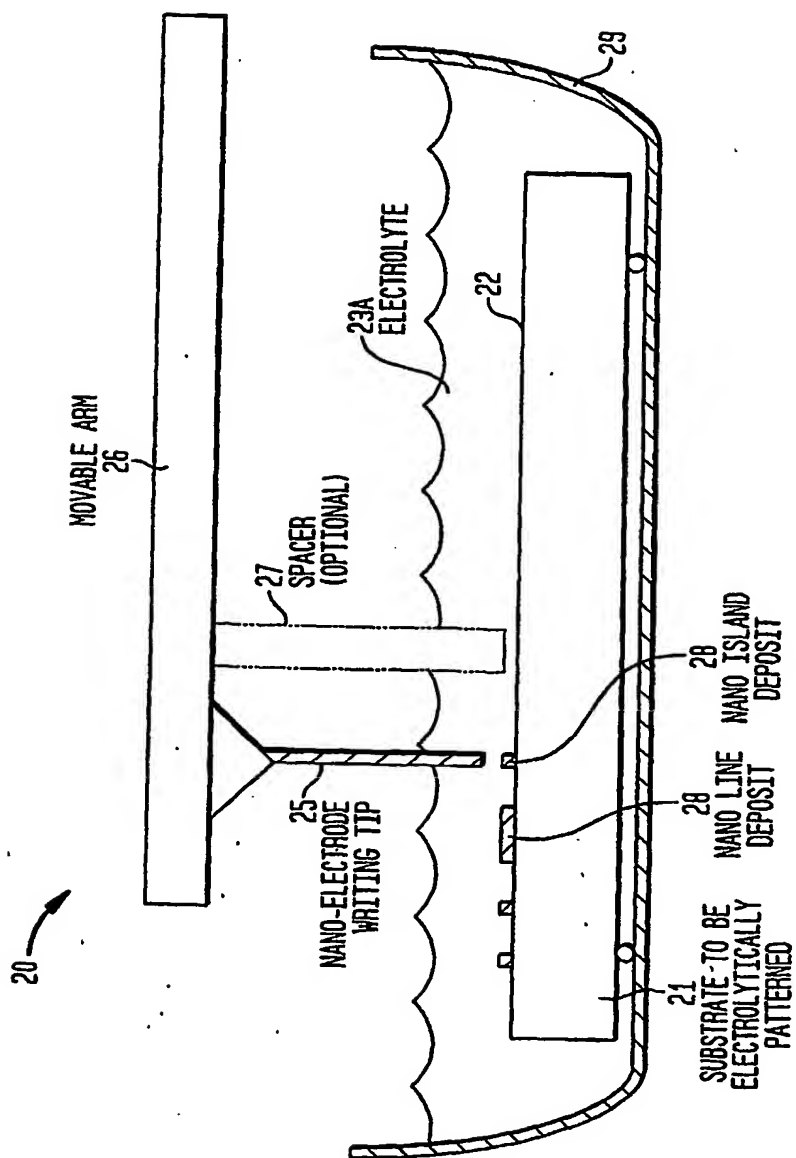
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FIG. 1



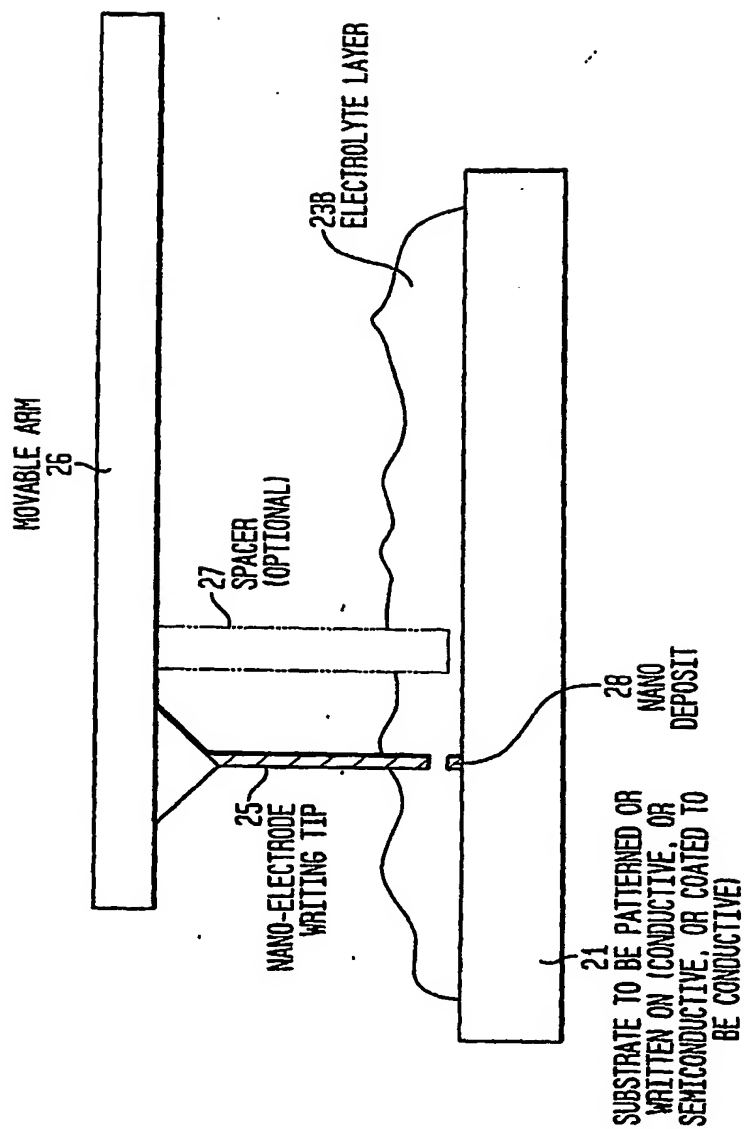
2/20

FIG. 2A



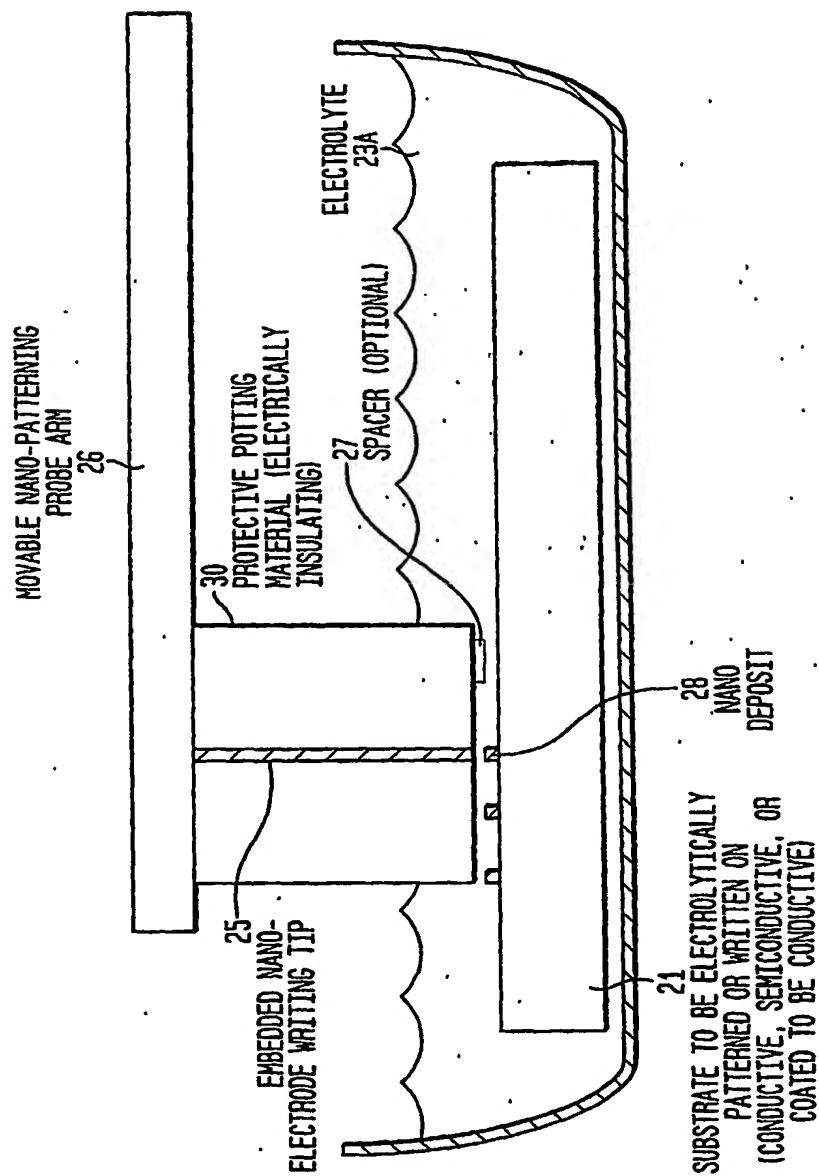
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FIG. 2B



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FIG. 3



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FIG. 4D

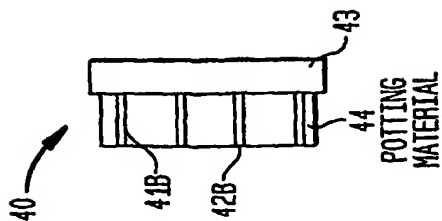


FIG. 4C

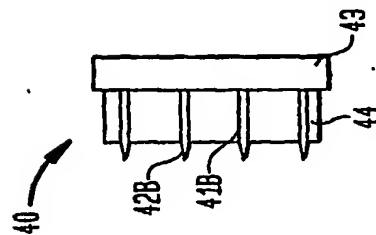


FIG. 4B

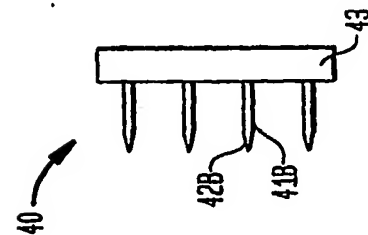
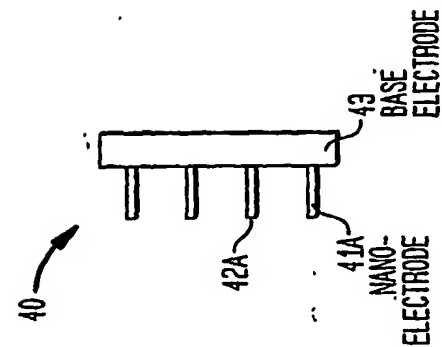
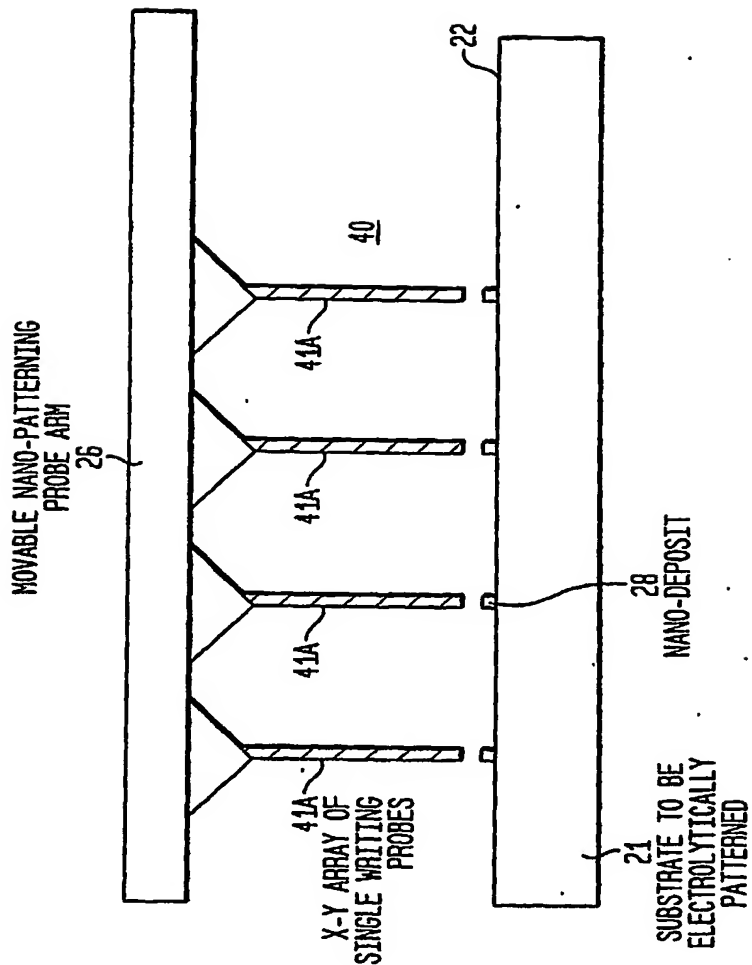


FIG. 4A



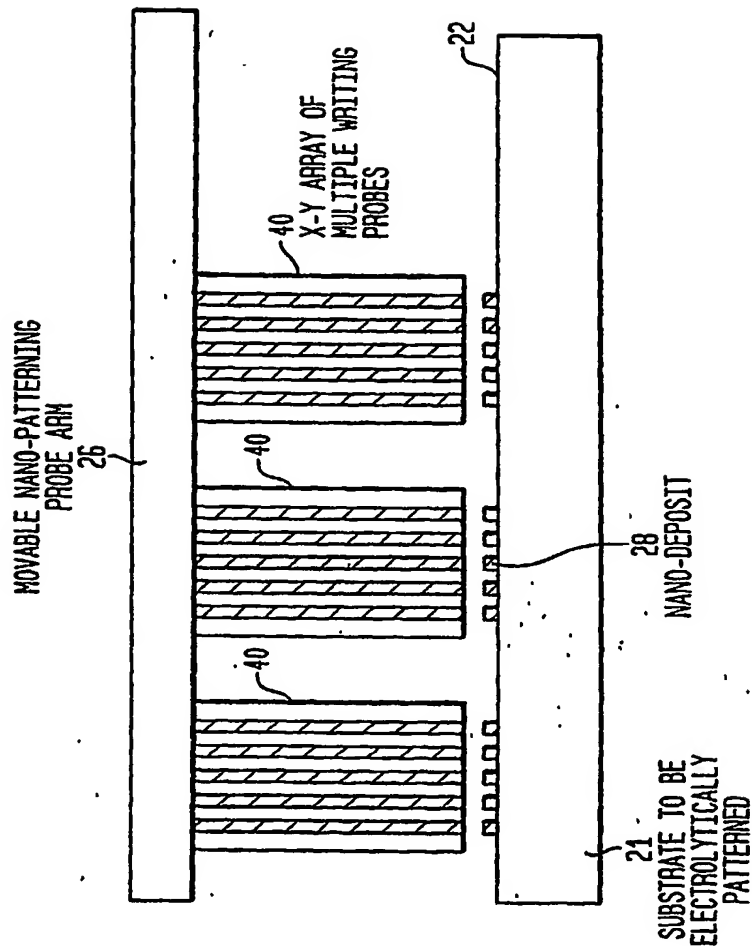
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FIG. 5



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FIG. 6



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FIG. 7C

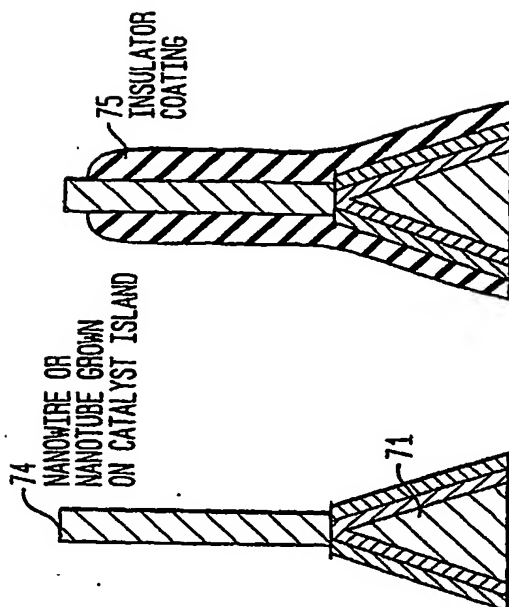


FIG. 7D

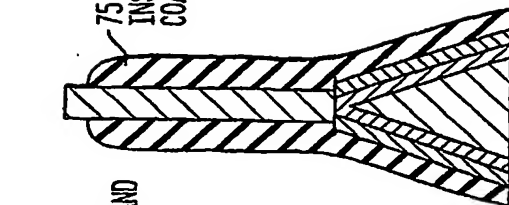


FIG. 7B

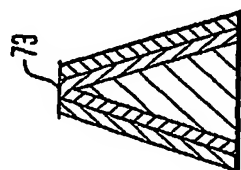
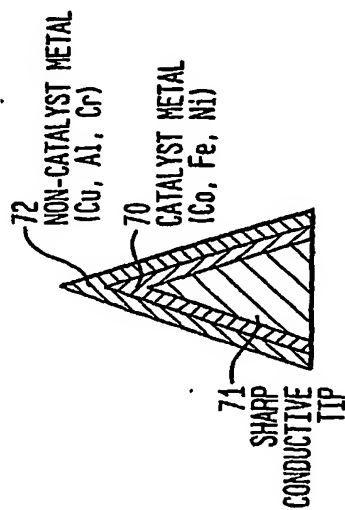


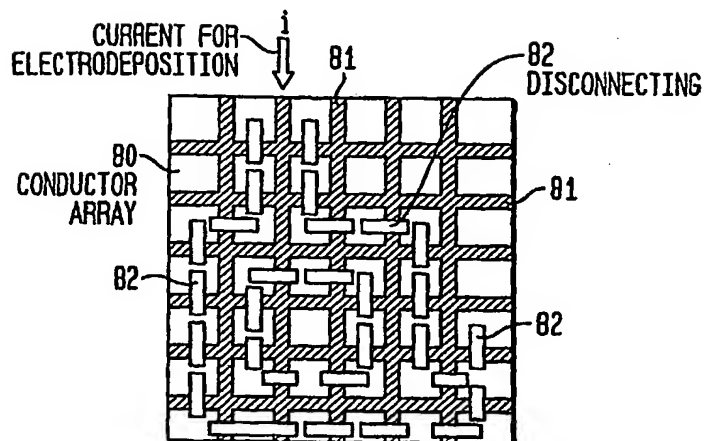
FIG. 7A



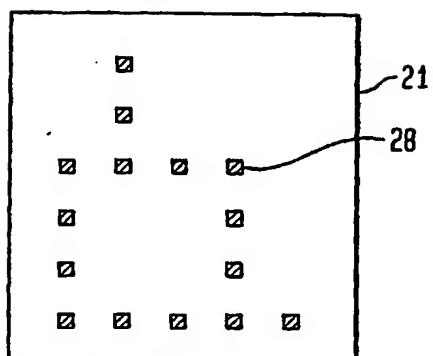


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**FIG. 8A**  
SELECTION OF  
ELECTRODES TO BE  
ACTIVATED BY  
WIRING  
REARRANGEMENT IN  
THE UPPER PART

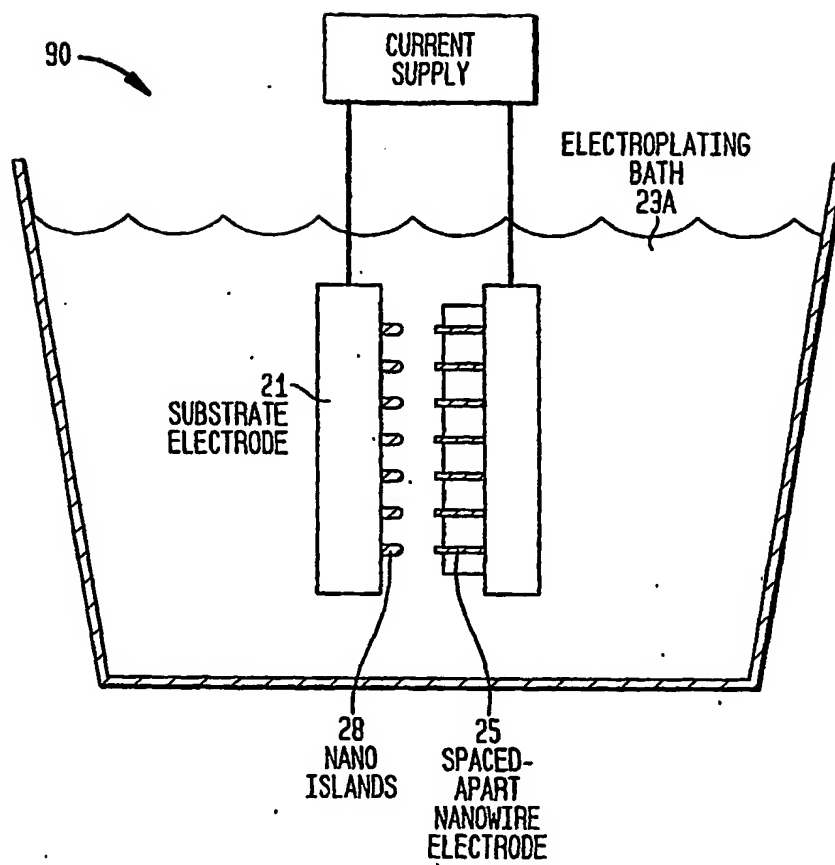


**FIG. 8B**  
RESULTANT NANO-  
DEPOSIT PATTERN ON  
SUBSTRATE



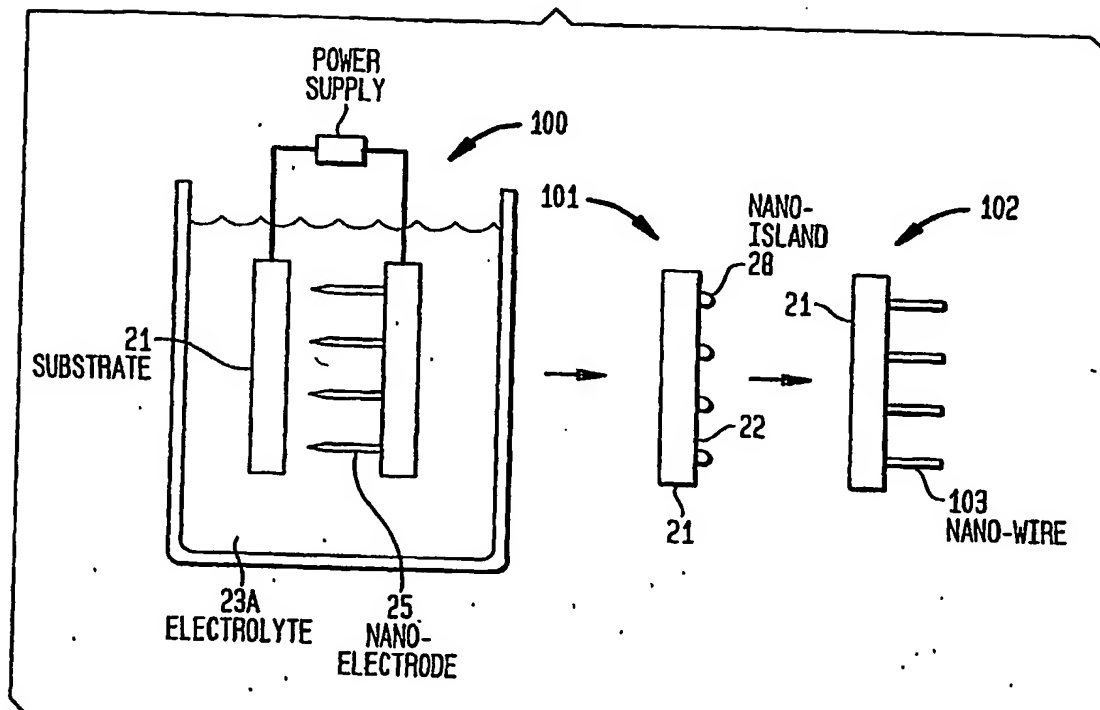
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FIG. 9



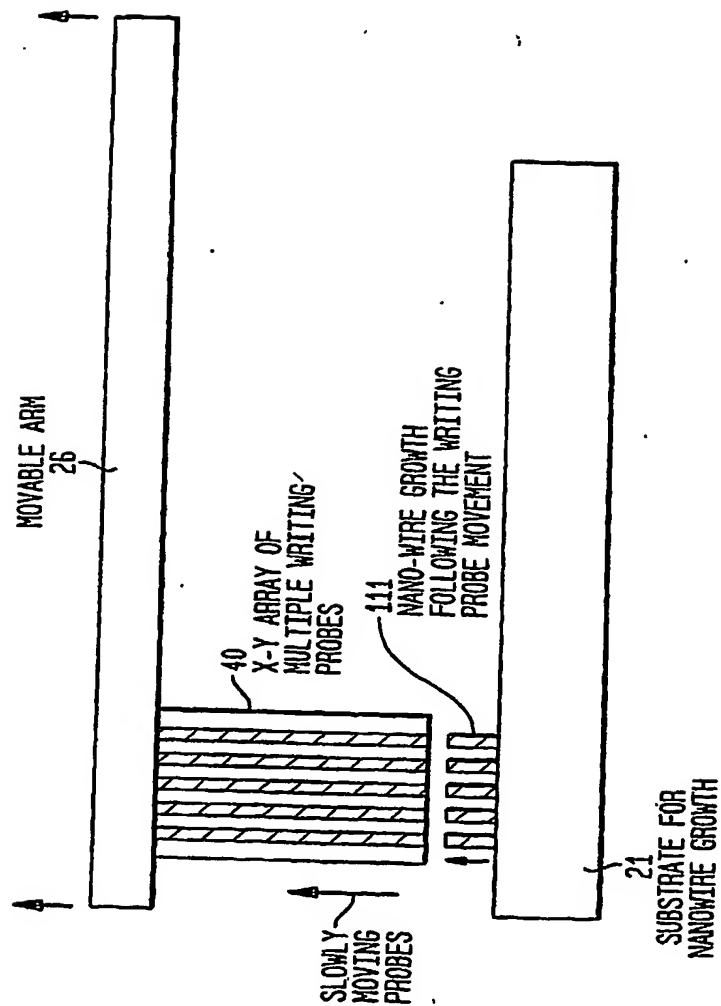
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FIG. 10



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FIG. 11



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FIG. 12D  
RECTANGULAR  
SPIRAL

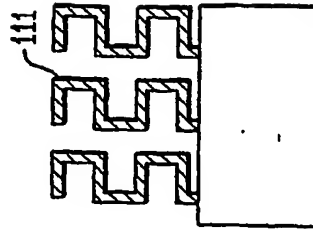


FIG. 12C  
SPIRAL

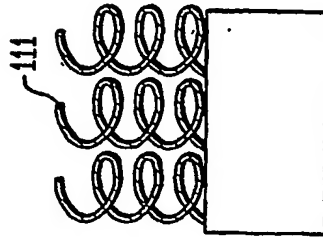


FIG. 12B  
ZIG-ZAG

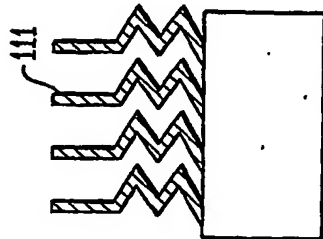
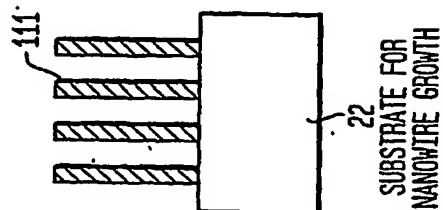


FIG. 12A  
STRAIGHT



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FIG. 13A

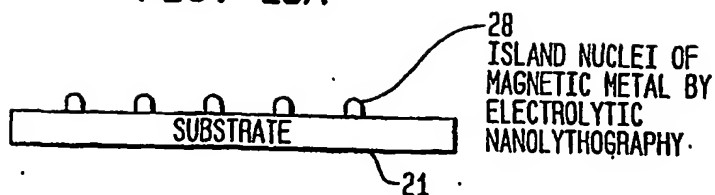


FIG. 13B

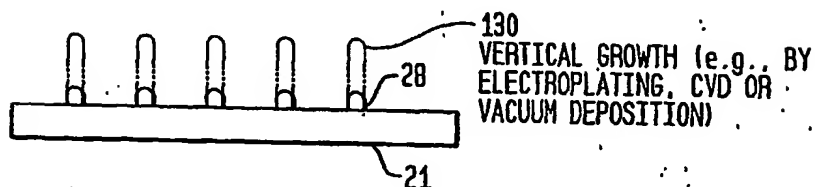


FIG. 13C

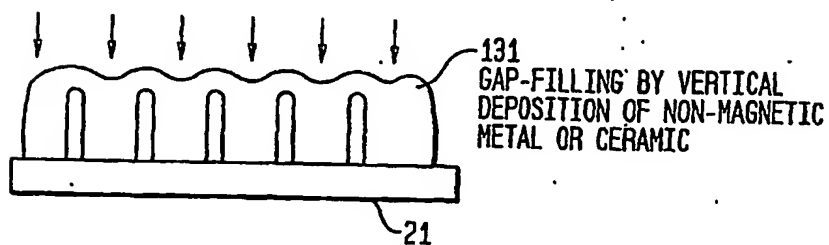
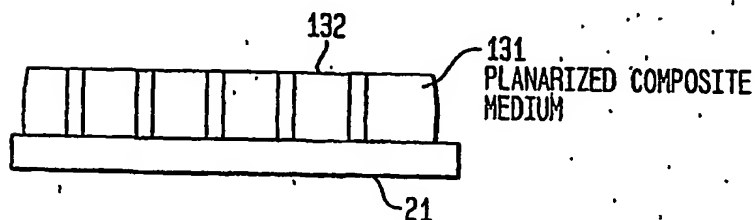
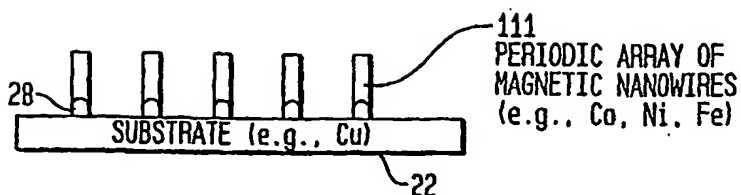
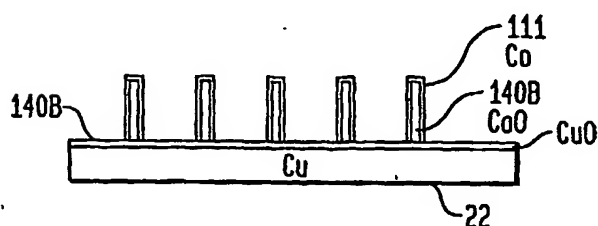
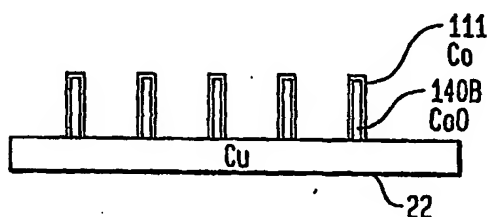
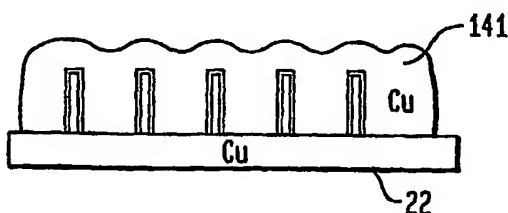
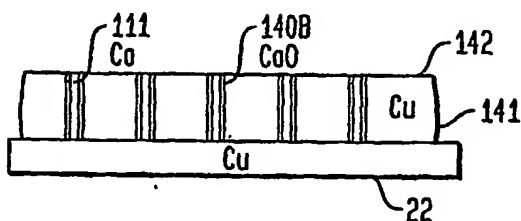


FIG. 13D



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**FIG. 14A****FIG. 14B**  
OXIDIZE OR CVD TO  
FORM INSULATOR SKIN**FIG. 14C**  
 $H_2$  REDUCTION**FIG. 14D**  
GAP-FILLING  
ELECTRODEPOSITION**FIG. 14E**  
PLANARIZE  
(e.g., BY CMP)

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FIG. 15A

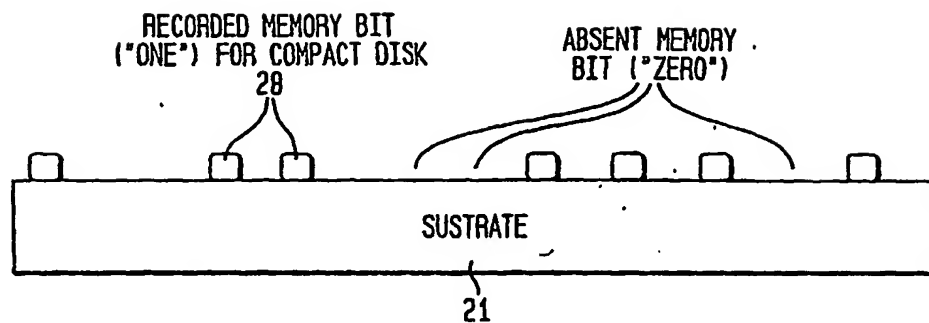
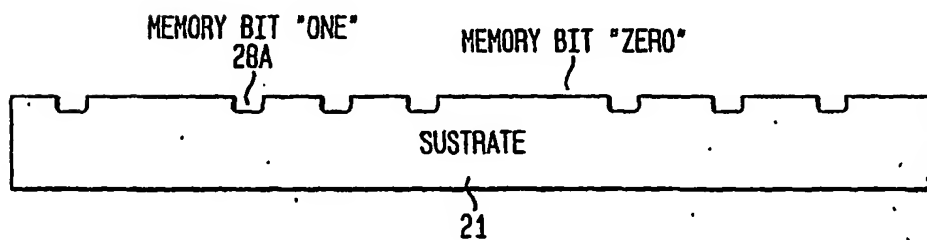
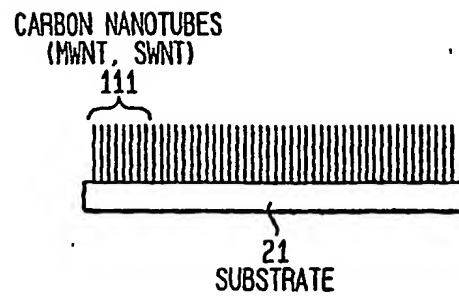
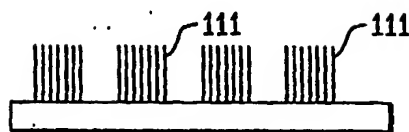
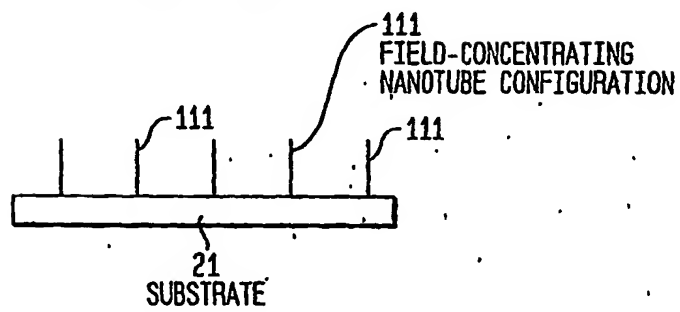


FIG. 15B



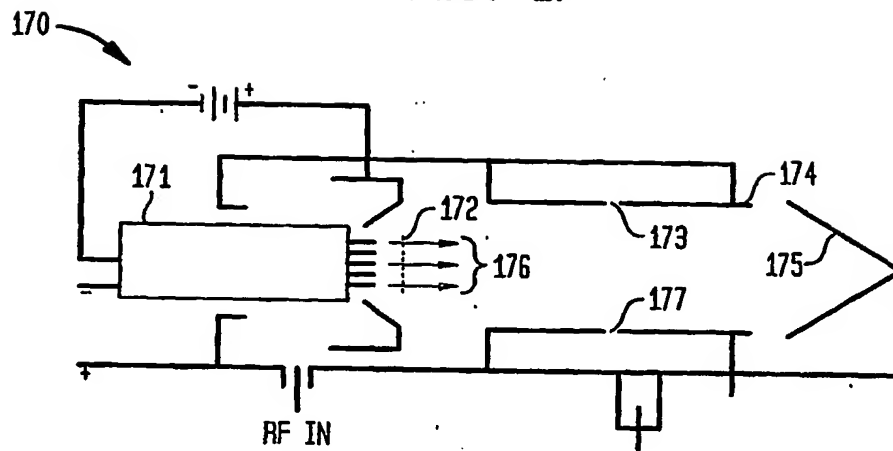


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**FIG. 16A****FIG. 16B****FIG. 16C****FIG. 16D**

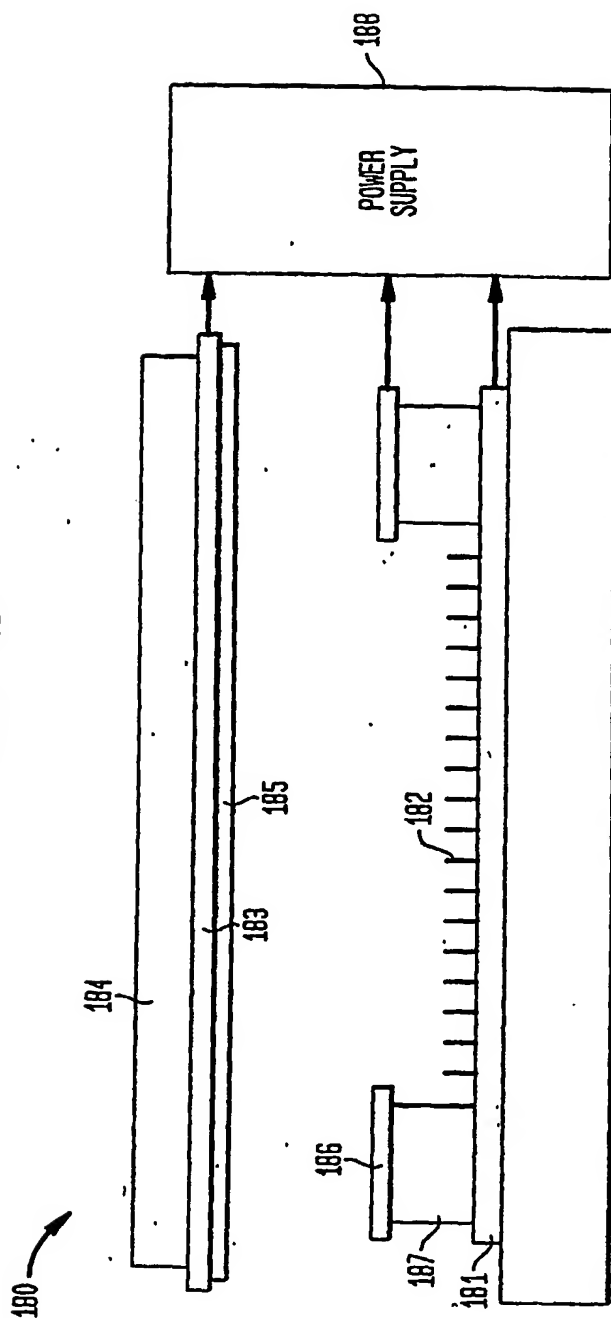
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FIG. 17



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FIG. 18



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FIG. 19

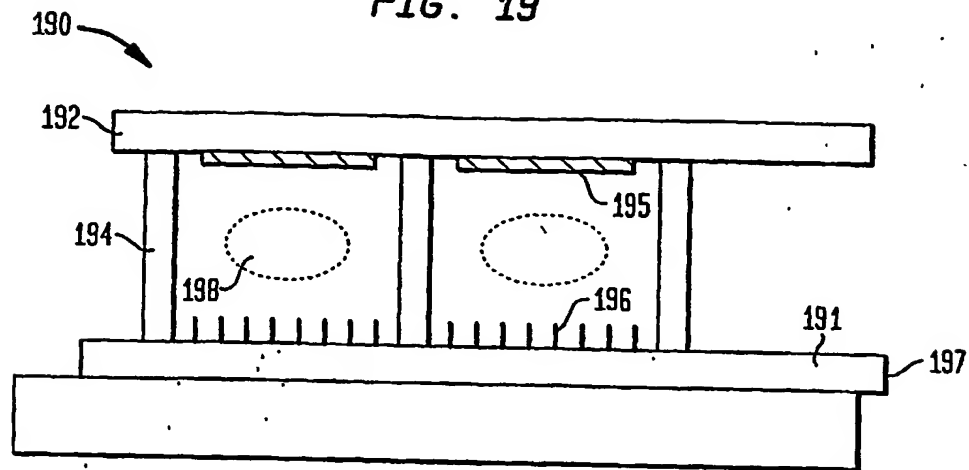


FIG. 20

